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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Selzer  
Application No.: 09/876,443  
Filing Date: June 7, 2001  
Title: Method of Improving X-Ray  
Lithography in the Sub 100nm  
Range to Create High Quality  
Semiconductor Devices

Docket No. 1520-006 (1426)  
Date: May 8, 2002  
Group Art Unit: 2882  
Examiner: I. Kiknadze  
FAX: 703 305-3594  
No. of pages sent:

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## Terminal Disclaimer Under 37 CFR 1.321(c)

Applicant disclaims term of any patent granted on this application extending beyond the term of  
US Patent 6,295,332.

The present application is commonly assigned with US Patent 6,295,332.

A fee sheet and the fee set forth in 37 CFR 1.20(d) is attached.

Any patent granted on the application shall be enforceable only for and during such period that  
said patent is commonly owned with the patent which formed the basis for the double patenting  
rejection (US Patent 6,295,332).

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Respectfully submitted,

For: Selzer et al.

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